# **Controlling the COF in CMP**

Len Borucki Araca Inc. (ret)

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#### **Significance of Friction in CMP**

Accurate, explanatory RR models are possible if we take the pad/wafer COF into account.

 $RR = RR_0 + c_p(V) \cdot COF(p, V) \cdot p$ 



L. Borucki, Y. Sampurno, A. Philipossian, ECS J. Solid State Sci. Technol. 12 044003 (2023)

#### **Measured Friction Coefficients**

The COF often follows a Stribeck lubrication curve, but with quirks that are poorly understood.



## **Motivations for this Study**

Understand how Stribeck curves work in CMP and how they relate to the process and consumables.

Explain the quirky behaviors.

Understand what we can do to change the COF if we need to.

## What Kind of Tribological Problem is CMP?

Because there is slurry and the surfaces are wetted, it is a **lubrication problem**.

We know, experimentally, that there is pad-wafer contact, so it is then a **mixed lubrication problem**.

Both the pad and wafer surface change significantly during polishing (intentionally!), making it a **time-dependent mixed lubrication problem**.

And then it gets worse ....

# **Mixed Elastohydrodynamic Lubrication (EHL) Model**

Example results from a coupled solution of the Reynolds and linear elasticity equations with CMP-relevant contact conditions and load balance.



This example: V

V = 0.6 m/s p = 0.4 PSI. Viscosity of water. 50  $\mu$ m tall parabolic (Hertzian) asperity 5  $\mu$ m summit radius of curvature 120 MPa elastic modulus, v=0.25

#### **Fluid and Solid Contact Pressures**





#### Variation of Contact Region C with Speed



## **Normalized Stribeck Curve**



## **Physical Parameters**

The model has six *physical* parameters, two of which are held constant here:

$\mu_0 = 10^{-3}$ Pa-s	Slurry viscosity (Newtonian).
ν =0.25	Pad Poisson ratio.

$$E^* = E/(1 - v^2)$$

$$R$$

$$\sigma$$

$$F = \frac{p}{\eta_c}$$

Effective pad modulus. Contacting pad asperity radius of curvature. Combined roughness (minimum contact fluid thickness) Applied force (or contact density) at pressure p.

# **Combined Roughness**

Contacts contain fluid assumed to have a minimum thickness  $\sigma$  determined by the pad & wafer *nanoscale combined roughness*.



## **Equivalent Sets of Parameters**

Stribeck curves have a degeneracy – many sets of parameters produce the same curve!



## **Dimensionless Parameters**

$$\begin{split} \Lambda &= 6\sqrt{2} \, \frac{\mu_0 R^{1/2}}{(\delta_0^E)^{3/2} E^*} V \equiv \Lambda_1 V & \text{Analog of the Sommerfeld number.} \\ \text{Independent variable used for plotting.} \\ \gamma &= \frac{\delta_0^E}{R} & \text{Ratio of elastic displacement to the radius of curvature} \\ \chi &= \frac{\sigma}{\delta_0^E} & \text{Ratio of the combined roughness to the elastic displacement} \\ \varphi &= \frac{F}{\delta_0^E R E^*} & \text{Normalized load} \end{split}$$

The last three parameters are *not independent* because  $\delta_0^E$  depends on the other physical parameters.

$$\chi = \left(\frac{3}{4}\gamma^{-1/2}\varphi\right)^{2/3} - 1$$

# **Stribeck Curve Characterization Method**

Construct a 5x5 point lattice  $(\gamma_i, \chi_j)$  by varying two independent parameters.

Calculate the normalized frictional Stribeck curves  $c_{ij}(\Lambda)$ .

Extract the "balance point" in the tail and the slope at the balance point and characterize with compact formulas.



#### **The Balance Point**



## **The Balance Point Slope Magnitude**



## **An Important Implication**

The product of the balance point and the slope magnitude depends only on  $\chi$ :

$$\Lambda_b \Lambda_b' = \frac{1}{2} \chi^{-\frac{3}{8}}$$

Furthermore, this also holds for the physical speed and slope since

$$V_b V_b' = \Lambda_b \Lambda_b'$$

#### **Parameter Extraction**

If we know the balance point speed and slope and know two other physical parameters, we can calculate *all* of the parameters for a Stribeck curve



Thus, if we know *E* and *F*, we can solve for *R* and determine everything else.

## **Analysis of a Real Stribeck Curve**

*Ex-situ* W buff: pre-polished wafers, IC-1000, commercial slurry, 3p x 3V, 30 s, Araca RDP-500.



# **Time Dependence**



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# **Final Remarks**

It is difficult to model friction in CMP, but the theory is looking hopeful.

The approach presented here agrees with and explains some of the more basic friction observations.

While idealized asperities were used to model data from conventional pads, the EHL software is much more general and is particularly suited to studying friction for microreplicated pads.

# **Thank You!**

## **Static Backup Slides**

## **Analysis of Real COF Data**



# **Time Dependence**

